

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Bhushan Sopori)	Group Art: 1797
)	
Serial No.:	10/535,291)	Examiner: SIEFKE, Samuel P.
)	
Filed:	May 16, 2005)	Atty. Dkt. No. NREL 02-15
)	
Title:	Wafer Characteristics via)	
	Reflectometry)	

RESPONSE TO RESTRICTION REQUIREMENT

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicant submits the following Response to the Restriction Requirement mailed July 10, 2008. Applicant elects without traverse, Group I including claims 1-40.

Although this election is being made without traverse, Applicant notes that separate classes of search have not been specified. Applicant believes that a thorough search of the prior art related to the claimed method (claims 1-40) would necessarily entail search and analysis of prior art related to a method of illuminating a wafer, measuring a reflectance of a wafer, and drawn to an alignable optical system (claims 41-58). Therefore, the search and examination would not create an undue burden on the Examiner.

If the search and examination of all the claims in an application can be made without serious burden, the Examiner must examine all of the claims on